PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

NAKAMURA, Tsuyoshi, et al.

Appln. No.: Not yet assigned.

Confirmation No.: Not yet assigned.

Filed: October 16, 2003

Docket No: Q78034

Continuation of 09/901,657

Group Art Unit: Not yet assigned.

Examiner: Not yet assigned.

For: NOVEL COPOLYMER, PHOTORESIST COMPOSITION, AND PROCESS FOR FORMING RESIST PATTERN WITH HIGH ASPECT RATIO

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Prior to examination, please amend the above-identified application as follows on the accompanying pages.

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